

In the Specification:

Please replace the paragraph at page 15, lines 16-20 of the Specification with the following amended paragraph:

Additionally, the surface of the substrate after the etch may be rough or smooth. A roughened surface may be provided, for example, by placing a thin layer of material, such as aluminum, between the etch mask and the substrate to create a micro-mask 315. When etched, the micro-mask 315 may act to roughen the surface of the substrate.